Tool ID: 505 Tool Location: 122

Equipment Information Sheet

JEOL 9500

Manager: Giovanni Sartorello 607-254-4853 Calls to staff phones will be automatically forwarded to

Backup: John Treichler 607-254-4949

Backup: Xinwei Wu 607-254-4934

their cell phones during accessible hours. At other times

leave a message or send them an email.

SAFETY

• No safety concerns during normal operation.

• No buddy system restrictions imposed on normal operation.

USAGE RESTRICTIONS

Please review electron beam lithography training materials in AFS (accessible on any CNF general use PC or Thin client) at

shares/public/processes_from_cnf_staff/ElectronBeamLithography/TrainingMaterials

SCHEDULING/SIGN-UP RESTRICTIONS

Minimum Tool Time: 30 minutes

- Put the beam current you plan to use in the "Beam Current" field in Nemo when you make the reservation.
- No more than three-hour reservation between the hours of 8 am and 8 pm, Monday through Friday.
- Maximum four reservations, or 12 hours reserved in advance at any time per person.
- The same user, group, or company must have at least three hours between any two reservations.

MATERIALS COMPATIBILITY CATEGORY

Tool Category 5: Class A and B Metals and Compounds Not Allowed Allowed Tool category 1/1E, 2, 3, and 4 materials Silicon Based Substrates and Films III/V compound Semiconductors Glass Substrates PECVD and ALD Films Cured organics and baked Photoresist CNF Class A, B, and Refractory metals Exposed Gold, Silver, Copper Alkali and Alkaline Compounds Organic/Biology Molecules preparedw/salt buffers High Vapor Pressure Materials (Mg, Ca, * Some tool restrictions on high vapor pressure Zn)*materials may apply Soft organic materials

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

• Fully baked resists only; do not load samples with unbaked resist or glue or anything that may degas.